



# 제 31회 한국반도체학술대회

## The 31st Korean Conference on Semiconductors

2024년 1월 24일(수)-26일(금) | 경주화백컨벤션센터(HICO)

2024년 1월 26일(금), 13:45-15:30

Room I(203), 2층

### D. Thin Film Process Technology 분과

#### [FI2-D] Atomic Layer Deposition - II

좌장: 김성근 책임(한국과학기술연구원), 최병준 교수(서울과학기술대학교)

FI2-D-1 13:45-14:00	Modulation of Atomic Layer Deposition for Improvement of Conformality on High Aspect Ratio Substrates Jiwon Kim <sup>1</sup> , Changbong Yeon <sup>2</sup> , Deok-Hyeon Cho <sup>2</sup> , Jaesun Jung <sup>2</sup> , and Bonggeun Shong <sup>1</sup> <sup>1</sup> Hongik University, <sup>2</sup> Soulbrain
FI2-D-2 14:00-14:15	Theoretical Screening of Tungsten Precursors toward Inherent Area-selective Atomic Layer Deposition of WO <sub>3</sub> between Nitride Substrates Su-Jin Kwon, Junhui Choi, Ju Hyeon Jung, and Bonggeun Shong Chemical Engineering, Hongik University
FI2-D-3 14:15-14:30	Enhanced Deposition Selectivity of High-k Dielectrics by Vapor-Dosed Self-Assembled Monolayer Inhibitors Combined with Selective Lift-Off Jeong-Min Lee and Woo-Hee Kim Department of Materials Science and Chemical Engineering, Hanyang University
FI2-D-4 14:30-14:45	Theoretical Analysis on the Influence of Ge Precursors toward Atomic Layer Deposition of Germanium Tellurides Hyeon Cho and Bonggeun Shong Hongik University
FI2-D-5 14:45-15:00	Growth Characteristics of Plasma-Enhanced Atomic Layer Deposition of SiN <sub>x</sub> by BTBAS and BDEAS with a Very High Frequency Plasma Source Young-Jin Lim <sup>1</sup> , Min-Jeong Rhee <sup>1</sup> , Ngoc Le Trinh <sup>2</sup> , Han-Bo-Ram Lee <sup>2</sup> , and Il-Kwon Oh <sup>1</sup> <sup>1</sup> Department of Intelligence Semiconductor Engineering, Ajou University, <sup>2</sup> Department of Materials Science and Engineering, Incheon National University
FI2-D-6 15:00-15:15	Temperature-dependent Surface Reactions in Atomic Layer Deposition of Titanium Nitride Jae Min Jang, Ju Hyeon Jung, and Bonggeun Shong Hongik University



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FI2-D-7 15:15-15:30	Theoretical Analysis of Niobium Precursors toward Inherent Area-selective Atomic Layer Deposition between Nitride Substrates Junhui Choi, Miso Kim, and Bonggeun Shong Hongik University
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